



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

#4 Formal Drawing
Accepted
6/11/01

Applicant: Furukawa, et al.

Docket No.: BU9-99-197

Serial No: 09/599,783

Group Art Unit: 2823

Filed: 6/22/00

Examiner: Eaton, K.

For: METHOD FOR ETCHING A SEMICONDUCTOR SUBSTRATE USING
GERMANIUM HARD MASK

Box Fee
Commissioner of Patents And Trademarks
Washington, D.C. 20231

Sir:

ATTENTION OFFICIAL DRAFTSMAN

Enclosed please find two (2) sheets of new formal drawings as amended as per
Examiner's requirements.

Respectfully submitted,

Kenneth C. Booth

Kenneth C. Booth
Reg. No. 42,342

DATE: May 31, 2001
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I HEREBY CERTIFY THAT THE CORRESPONDENCE TO WHICH THIS STATEMENT IS AFFIXED IS BEING DEPOSITED WITH THE
UNITED STATES POSTAL SERVICE, POSTAGE PAID FIRST CLASS MAIL IN AN ENVELOPE ADDRESSED TO BOX FEE,
COMMISSIONER OF PATENTS AND TRADEMARKS, WASHINGTON, D. C., 20231, ON: May 31, 2001

SIGNED: *Heather Clark*